

#9 1771
DOCKET NO: M00925.70067.US

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Vanessa Z.H. Chan et al.
Serial No: 09/720,710
Confirmation No: 5662
Filed: July 2, 1999
For: Periodic Porous and Relief Nanostructured Articles
Art Unit: 1771

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CERTIFICATE OF MAILING UNDER 37 C.F.R. §1.8(a)

The undersigned hereby certifies that this document is being placed in the United States mail with first-class postage attached, addressed to Commissioner for Patents, Washington, D.C. 20231, on the 20 day of February 2003.

Kouen M. DiAngelo
Signature

COMMISSIONER FOR PATENTS
WASHINGTON, D.C. 20231

Sir:

Transmitted herewith is/are the following document(s):

- ☒ Information Disclosure Statement
- ☒ Form PTO-1449 and References
- ☒ Return Receipt Postcard

If the enclosed papers are considered incomplete, the Mail Room and/or the Application Branch is respectfully requested to contact the undersigned at (617) 720-3500, Boston, Massachusetts.

No fee is due. If it is determined that a fee is due, it may be charged to the account of the undersigned, Deposit Account No. 23/2825. A duplicate of this sheet is enclosed.

Respectfully Submitted,

Michael J. Pomianek

Timothy J. Oyer, Reg. No. 36,628
Michael J. Pomianek, Reg. No. 46,190
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Karen M. D'Angelo
Signature

Commissioner for Patents
Washington, D.C. 20231

**STATEMENT FILED PURSUANT TO THE DUTY OF
DISCLOSURE UNDER 37 CFR §§1.56, 1.97 AND 1.98**

Sir:

Pursuant to the duty of disclosure under 37 C.F.R. §§1.56, 1.97 and 1.98, the Applicant requests consideration of this Information Disclosure Statement.

PART I: Compliance with 37 C.F.R. §1.97

This Information Disclosure Statement has been filed before the mailing date of a first Office Action on the merits in the above-identified case.

No fee or certification is required.

PART II: Information Cited

The Applicant hereby makes of record in the above-identified application the information listed on the attached form PTO-1449 (modified). The order of presentation of the references should not be construed as an indication of the importance of the references.

The Applicant hereby makes the following additional information of record in the above-identified application.

The above-identified U.S. application claims priority to International application serial no. PCT/US99/15068. If the Examiner has not had the benefit of review of the file history of

PCT/US99/15068, then he/she is asked to contact the undersigned, who will provide a copy of same.

The following co-pending applications that may contain subject matter related to this application are enclosed unless the earlier application is identified herein and is relied upon for an earlier filing date under 35 U.S.C. §120, and the copy was provided in the earlier application:

<u>Serial No.</u>	<u>Filing Date</u>	<u>Inventor(s)</u>	<u>Atty Docket No.</u>
10/146,775	May 16, 2002	Y. Fink et al.	M00925.70117.US

PART III: Remarks

Documents cited anywhere in the Information Disclosure Statement are enclosed unless otherwise indicated. It is respectfully requested that:

1. The Examiner consider completely the cited information, along with any other information, in reaching a determination concerning the patentability of the present claims;
2. The enclosed form PTO-1449 be signed by the Examiner to evidence that the cited information has been fully considered by the Patent and Trademark Office during the examination of this application;
3. The citations for the information be printed on any patent which issues from this application.

By submitting this Information Disclosure Statement, the Applicant makes no representation that a search has been performed, of the extent of any search performed, or that more relevant information does not exist.

By submitting this Information Disclosure Statement, the Applicant makes no representation that the information cited in the Statement is, or is considered to be, material to patentability as defined in 37 C.F.R. §1.56(b).

By submitting this Information Disclosure Statement, the Applicant makes no representation that the information cited in the Statement is, or is considered to be, in fact, prior art as defined by 35 U.S.C. §102.

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Conf. No. 5662

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Art Unit: 1771

Notwithstanding any statements by the Applicant, the Examiner is urged to form his own conclusion regarding the relevance of the cited information.

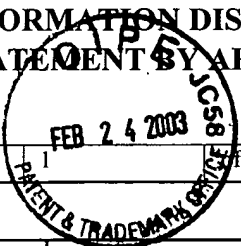
An early and favorable action is hereby requested.

Respectfully submitted,
Vanessa Z.H. Chan et al., *Applicant*

By: Michael J. Pomianek
Timothy J. Oyer, Reg. No. 36,628
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Docket No. M00925.70067.US
Date: February 19, 2003
XNDDX

FORM PTO-1449/A and B (Modified)		APPLICATION NO.: 09/720,710	ATTY. DOCKET NO.: M00925.70067.US
INFORMATION DISCLOSURE STATEMENT BY APPLICANT		FILING DATE: July 2, 1999	CONFIRMATION NO.: 5662
		APPLICANT: Vanessa Z.H. Chan et al.	
		GROUP ART UNIT: 1771	EXAMINER: Unassigned
Sheet 1	4		



U.S. PATENT DOCUMENTS

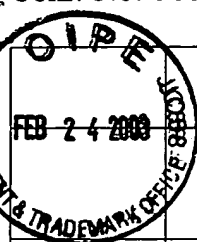
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OTHER ART — NON PATENT LITERATURE DOCUMENTS

Examiner's Initials	Date No	Include name of the author (in CAPITAL LETTERS) title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, relevant page(s), volume-issue number(s), publisher, city and/or country where published.	Translation (Y/N)
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